

Notice of References Cited	Application/Control No. 10/544,783		Applicant(s)/Patent Under Reexamination TERASHIMA ET AL.	
	Examiner PAPE SENE		Art Unit 2812	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-			
	B	US-			
	C	US-			
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FOREIGN PATENT DOCUMENTS

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	Q					
	R					
	S					
	T					

NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Menachem Natan, "Anomalous first-phase formation in rapidly thermal annealed, thin-layered Si/Ni/Si films" August, 4th 1986, Applied Physics Letters, Vol. 49 Issue 5, pages 257-259.
	V	D. Mangelick et al., "Formation of Ni silicide from Ni(Au) films on (111)Si" April, 15th 1996, Journal of Applied Physics, Vol. 79 Issue 8, Pages 4078-4086.
	W	B. Bokhonov et al., "In-situ investigation of the formation of nickel silicides during interaction of single-crystalline and amorphous silicon with nickel" April, 26th 2001, Journal of Alloys and Compounds, Vol. 319, Pages 187-1195.
	X	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.